

Double Patterning and Hyper-Numerical Aperture Immersion Lithography

- 1) What are the main differences in the three techniques of double patterning lithography (litho-etch litho-etch, litho-freeze litho-etch, and self-aligned double patterning)?
- 2) Which techniques are used in the fabrication of memory devices and which are used for the fabrication of logic devices?
- 3) What is the main difference(s) between hyper-numerical aperture immersion lithography and conventional dry projection lithography?
- 4) What are two disadvantages of hyper-numerical aperture immersion lithography?